Electronic Supplementary Information

Logic Inverters Based on the Property Modulated Si Nanowires by Controlled Surface Modifications

Kyeong-Ju Moon, ^a Tae-II Lee, ^a Woong Lee, ^b and Jae-Min Myoung^{* a}

^a Department of Materials Science and Engineering, Yonsei University, 134 Shinchondong, Seoul, 120-749, Korea. Fax:

+82-2-365-2680; Tel: +82-2-2123-2843; E-mail: jmmyoung@yonsei.ac.kr ^b School of Nano & Advanced Materials Engineering, Changwon National University, 9 Sarim-Dong, Changwon, Gyoungnam 641-773, Korea.



Figure S1. TEM images of heat treated *n*-type Si NWs for (a) 10 and (b) 20 min at 900 °C. The surface of Si NWs was oxidized to SiO₂ at the rate of 1.3 nm a minute. The surface of NW is smoother than as synthesized NW.

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Figure S2. Output characteristics (I_{DS} - V_{DS}) of (a) as-synthesized *n*-type Si NWs and heat treated Si NWs for (b) 10, (c) 20, and (d) 30 min.

	as-synthesized	10 min	20 min	30 min
Mobility (cm²/Vs)	1 ~ 40	40 ~ 100	110 ~ 440	190 ~ 450
Subthreshold swing (V/decade)	1.4 ~ 4.0	1.4 ~ 2.1	1.4 ~ 2.3	1.3 ~ 2.1
Threshold voltage (V_{th})	-2 ~ 9	-3 ~ 5	-6 ~ 1	-12 ~ -5
Yield (%)	9	67	92	89

Table S3. The electrical properties in each state were represented by numerical table

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Figure S4. Typical I_{DS} - V_{DS} relations measured on a test structure prepared by depositing Ag and Au electrodes on cured PVP/SiO₂ without Si NWs.